

EV 026161597

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. .... 09/026,042  
Priority Filing Date ..... February 19, 1998  
Inventor ..... Sujit Sharan et al.  
Assignee ..... Micron Technology, Inc. and Applied Materials, Inc.  
Priority Group Art Unit ..... 1763  
Priority Examiner ..... P. Hassanzadeh Ph.D.  
Attorney's Docket No. .... MI22-1902  
Title: RF Powered Plasma Enhanced Chemical Vapor Deposition Reactor and Methods  
of Effecting Plasma Enhanced Chemical Vapor Deposition



**INFORMATION DISCLOSURE STATEMENT**

References - - See attached Form PTO-1449

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a divisional application of co-pending application Serial No. 09/026,042, filed February 19, 1998, upon which the above-identified application relies for a priority date under 35 U.S.C. §120. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. §1.98(d) and MPEP §609(2). As a courtesy, Applicant submits copies of the cited foreign references and articles for review.

Citation of these references is respectfully requested.

Respectfully submitted,

Date: 324.14.2002

Frederick M. Fliegel, Ph.D.  
Reg. No. 36,138

Form PTO-1449

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PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.  
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## U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	5,942,075	08/24/99	Nagahata et al.			
	AB	5,919,332	07/06/99	Koshiishi et al.			
	AC	5,900,103	05/04/99	Tomoyasu et al.			
	AD	5,865,937	02/02/99	Shan et al.			
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	AF	5,716,534	02/10/98	Tsuchiya et al.			
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	AI	5,607,542	03/04/97	Wu et al.			
	AJ	5,605,637	02/25/97	Shan et al.			
	AK	5,567,267	10/22/96	Kazama et al.			

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		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL	WO 98/32154	1998	PCT				
	AM	EPO 831 679 A1	1998	EPO				
	AN	EPO 776 991 A1	1997	EPO				
	AO	EPO 742 577 A2	1996	EPO				
	AP	0 686 708 A1	1995	EPO				

## OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

	AR		Radio Frequency Matching for Helicon Plasma Sources	J.P. Rayner et al., J. Vac. Sci. Technol. A 14(4) Jul/Aug. 1996, pages 2048-2055.
	AS			
	AT			

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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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	AA	5,468,296	11/21/95	Patrick et al.			
	AB	5,439,524	08/08/95	Cain et al.			
	AC	5,433,786	07/18/95	Hu et al.			
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							Yes	No
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	AN	0 641 150 A1	1995	EPO				
	AO	0 552 491 A1	1993	EPO				
	AP	2 663 806	1991	France				

## OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

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	AA	4,585,516	04/29/86	Corn et al.			
	AB	5,853,484	12/29/98	Jeong			
	AC	6,159,867	12/12/00	Sharan et al.			
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		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL	5-175163	1991	Japan				
	AM	WO 89/02695	1989	PCT				
	AN	08-031806	2000	Japan				
	AO							
	AP							

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